

Fig. 1

PRESSURE CYCLE 172		PURGE CYCLE 182	
Insert substrate into chamber.	Close non-sealing flow restrictor.	Admit first deposition gas to pressurize chamber.	Soak substrate in deposition gas.

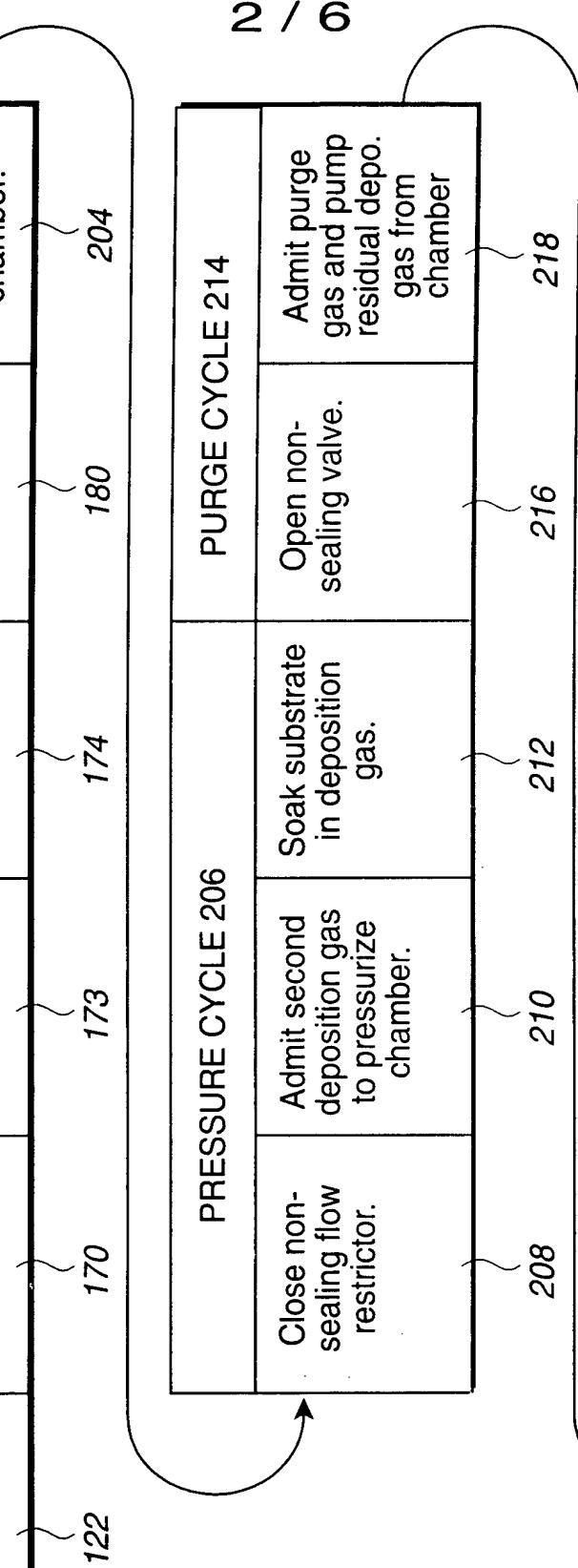


Fig. 2A
Fig. 2B

Fig. 2

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Fig. 2A

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1.0000
0.5000
0.1000
0.0500

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PRESSURE CYCLE 172		PURGE CYCLE 182	
Close non-sealing flow restrictor.	Admit first deposition gas to pressurize chamber.	Soak substrate in deposition gas.	Open non-sealing restrictor.
			Admit purge gas and pump residual depo. gas from chamber.
170		204	
173		180	
174		182	
PRESSURE CYCLE 206		PURGE CYCLE 214	
Close non-sealing flow restrictor.	Admit second deposition gas to pressurize chamber.	Soak substrate in deposition gas.	Open non-sealing valve.
			Admit purge gas and pump residual depo. gas from chamber.
208		218	
210		216	
212		220	
214		222	

out of cycle
120 sec A
120 sec B
120 sec C

Fig. 23

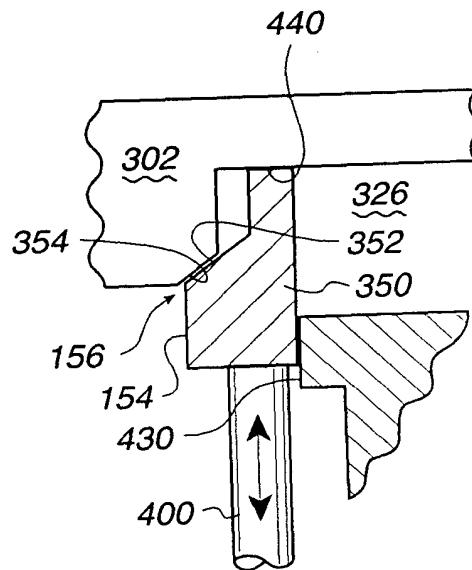


Fig. 3

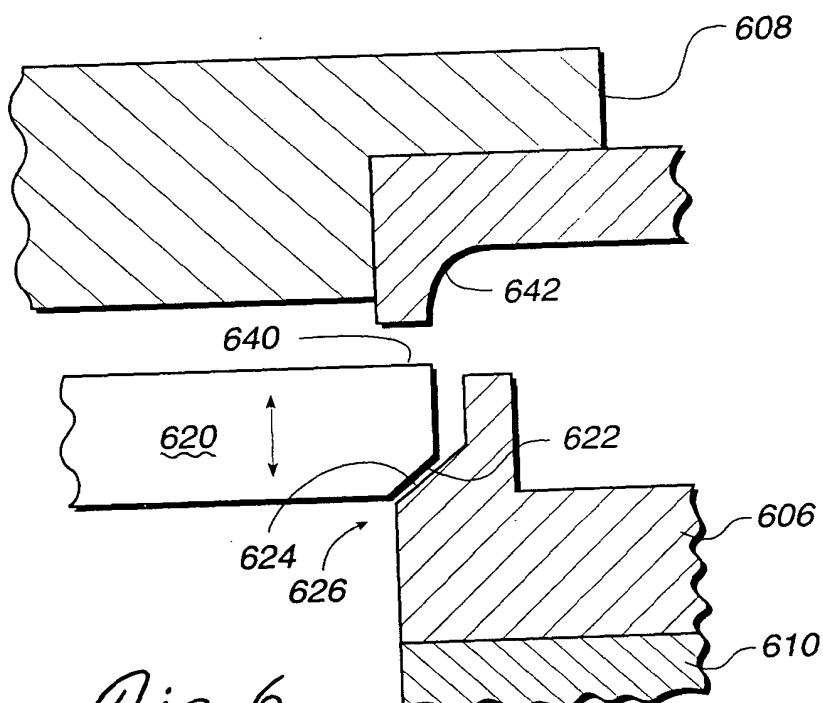


Fig. 6

440

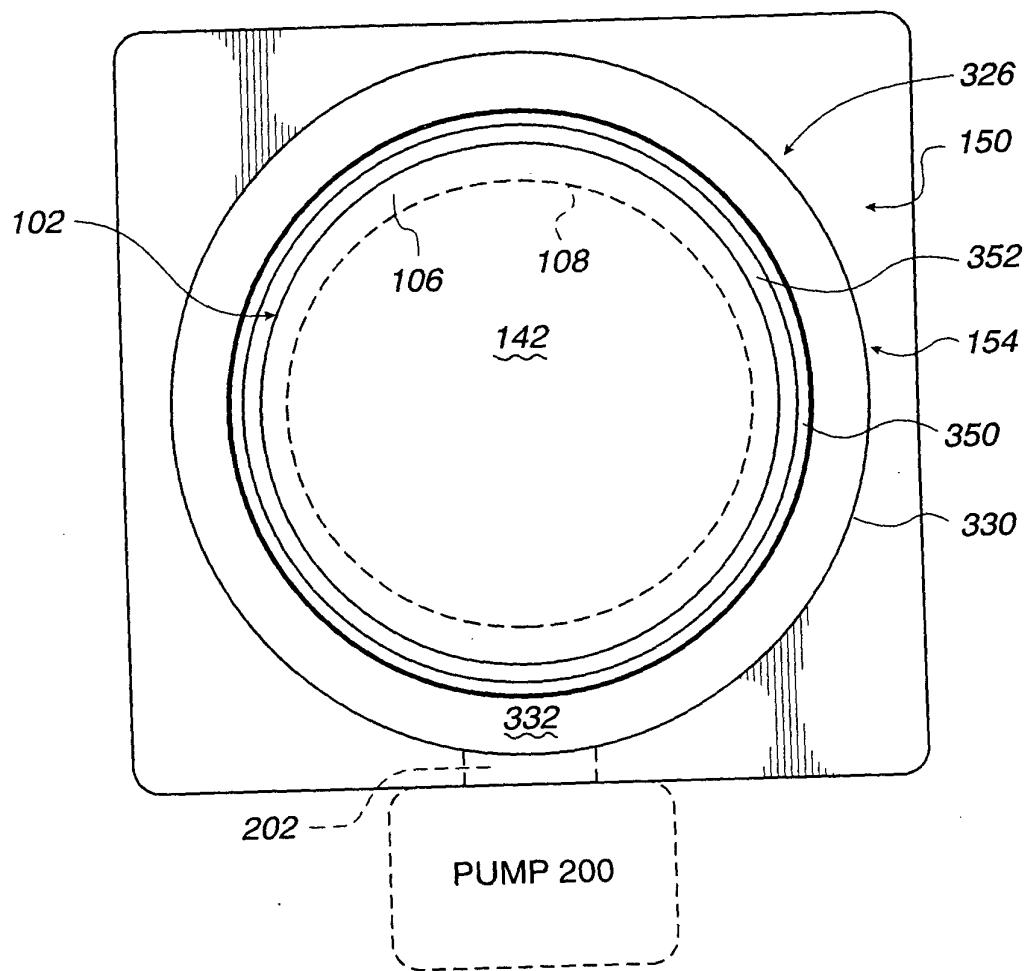


Fig. 4

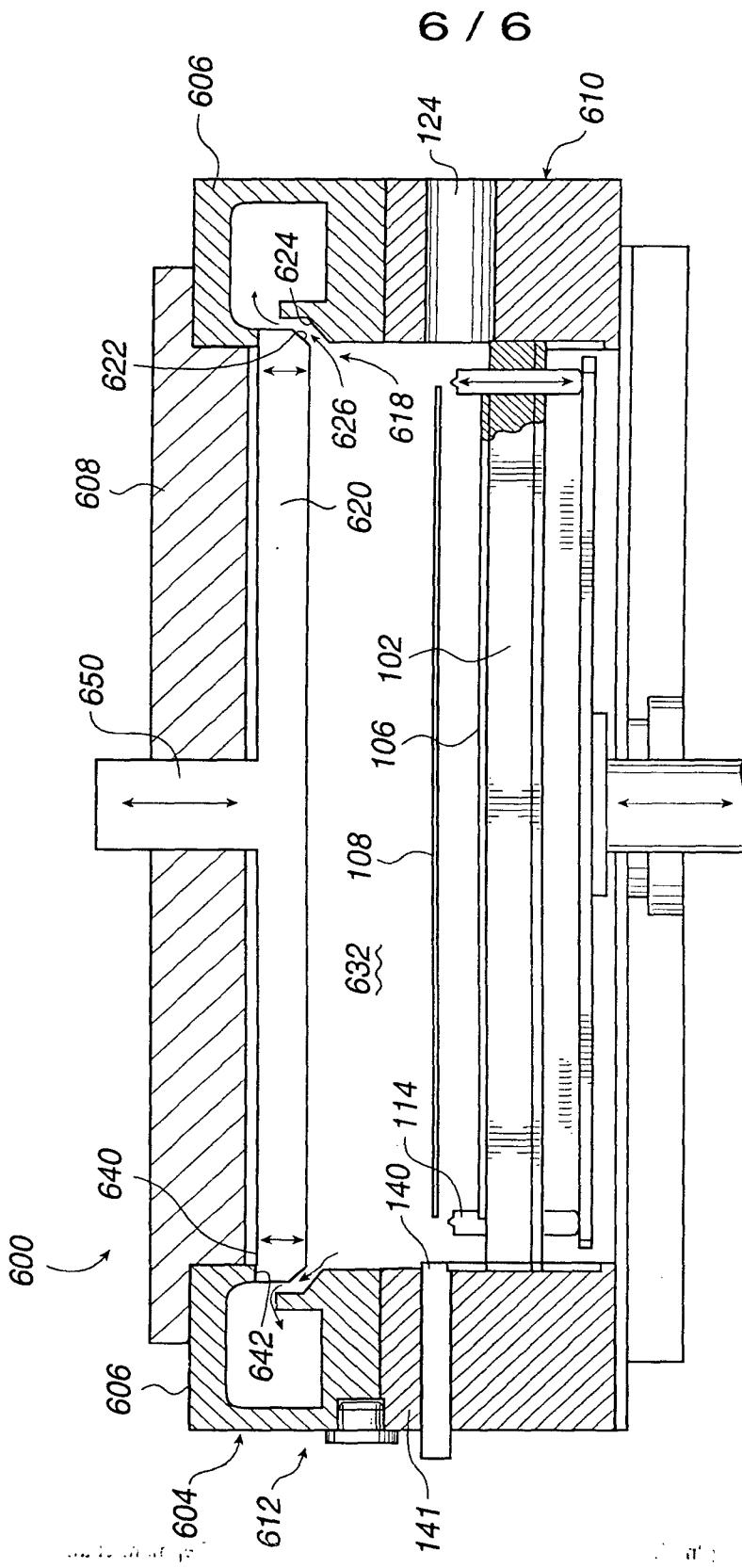


Fig. 5